Oral presentation | 8 Plasma Electronics | 8.2 Plasma deposition of thin film, plasma etching and surface treatment

[18a-C309-1~10] 8.2 Plasma deposition of thin film, plasma etching and surface treatment
Keiichiro Urabe (Kyoto Univ.), Takayoshi Tsutsumi (名大)
Wed. Sep 18, 2019 9:00 AM - 12:00 PM  C309 (C309)
△ : Presentation by Applicant for JSAP Young Scientists Presentation Award
▲ : English Presentation
▼ : Both of Above
No Mark : None of Above

10:00 AM - 10:30 AM

[18a-C309-5][INVITED] Cyclic etching of tin-doped indium oxide using hydrogen-induced modified layer
Keywords: JSAP Paper Award Speech